Remarks - General

By the amendment, Applicants have amended the claims as specified by the Examiner, except for the following typographic errors found on Page 5 of the Office Action:

Page 5, Claim 25, of the Office Action:

- Line 4, change "electrostatic field" to --electrostatic potential--:
- Line 5, after "topside" add --surface of said high transmission surface--.

These phrases should read:

- Line 3, change "electrostatic field" to --electrostatic potential--:
- Line 4, after "topside" add --surface of said high transmission surface--. Claim 25 was amended with the above corrections.

Page 5, Claim 27, of the Office Action:

Line 35, after "topside" add --surface of said high transmission surface--.

This phrase should read:

• Line 3, after "topside" add --surface of said high transmission surface--; Claim 27 was amended with the above correction.

In addition to the formal changes specified by the Examiner, Applicants have amended Claim 15 with an additional formal change as follows:

Claim 15.

 Line 4, adding the word "sources" after the phrase "capture ionization", to fully describe the types of sources.

Number: 09/877,167 (Sheehan et al.) GAU: Hai C. Pham / 2861 Ammt. D, contd. 11

Conclusion

Applicants submit the claims are now in proper form. Therefore they submit that this application is now in condition for allowance, which action they respectfully solicit.

Very Respectfully.

Edward W Sheehan

Ross C Willoughby

-----Applicants Pro Se--

Chem-Space Associates

655 William Pitt Way, Pittsburgh, PA 15238

Telephone: 412-826-3013 or 412-963-6881, Fax: 412-963-6882

E-mails: E.W. Sheehan (ews@lcms.com) and R.C. Willoughby (ross@lcms.com)

Certificate of Mailing

I hereby certify that this correspondence, and attachments, if any, will be deposited with the United States Postal Service by Priority Mail, postage prepaid, in an envelope addressed to "Box Non-Fee Amendments, Commissioner for Patents, PO Box

1450, Alexandria, VA 22313-1450" on the following date: 2003 Dec 3

Inventor's Signature:

Edward W Sheehan, Applicant